

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 2003-279715

(43)Date of publication of application : 02.10.2003

(51)Int.Cl.

G02B 5/08
C22C 5/06
C23C 14/34
G02F 1/1335

(21)Application number : 2002-083167

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(22)Date of filing : 25.03.2002

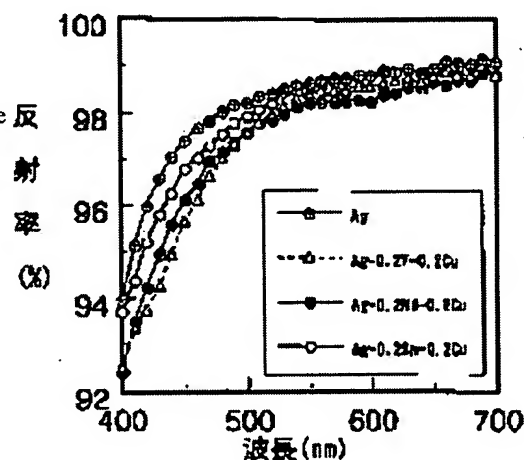
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(54) PLANAR DISPLAY UNIT, Ag ALLOY-BASED REFLECTIVE FILM THEREFOR AND SPUTTERING TARGET MATERIAL FOR Ag ALLOY- BASED REFLECTIVE FILM FORMATION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide an Ag alloy-based reflective film improving adhesion and patterning to a substrate, by making a reflectance a constant value in a visible range after maintaining a high reflectance and providing thermal resistance and corrosive resistance, and to provide a sputtering target material for forming the Ag alloy-based reflective film, and a high quality and low power consumption planar display unit.

SOLUTION: The Ag alloy-based reflective film for the planar display unit comprises 0.1-0.5 at.% of Sm, 0.1-0.5 at.% in total of Au and/or Cu, and the residue of substantially Ag. In addition, the planar display unit uses the Ag alloy-based reflective film having the above composition. The sputtering target material for the Ag alloy-based reflective film comprises 0.1-0.5 at.%, 0.1-0.5 at.% in total of Au and/or Cu, and the residue of substantially Ag.



LEGAL STATUS

[Date of request for examination]

21.02.2005

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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